October 20 (Tue.), 2026

[Oral 05] AI & ML for CMP / Process Control

16:55-17:55

International Conference Hall (B1F)

● Session Chair: Chao-Cheng Arthur Chen (NTUST, Taiwan)

16:55-17:15 [Oral 05-1] AI-Enabled CMP Process Optimization in Advanced Semiconductor Manufacturing

Cheng Zhongyao (Inst. for Infocomm Research (I2R), Singapore), Su Myat Noe, Leong Lup San, Chen Gim Guan (Inst. for Microelectronics (IME), Singapore), Qian Peisheng, Ata Kircali Sezin, Gopinathan Arjunan, Ashish James (Inst. for Infocomm Research (I2R), Singapore), and Jun Hyunsu (Inst. for Microelectronics (IME), Singapore)

17:15-17:35 [Oral 05-2] Digital-Twin-Based Evaluation of Virtual Metrology for APC Performance in CMP

Seungchoun Choi, Yonghwan Yim, and Semyeong Oh (Amously Inc., Korea)

17:35-17:55 [Oral 05-3] Accelerating CMP Model Development Using Machine Learning for Early Manufacturability Risk Detection

Ushasree Katakamsetty (Globalfoundries Singapore Pte. Ltd., Singapore), Henning Turnow, Boris Vasilev (Globalfoundries Dresden, Germany), Stefan Nikolaev Voykov (Globalfoundries, Bulgaria), Ruben Ghulghazaryan, Davit Piliposyan (Siemens Industry Software, Armenia), and Jeff Wilson (Siemens EDA, USA)